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- (71) **Applicant:** MERCK PATENT GMBH [DE/DE]; Frankfurt
Strasse 250, 64293 Darmstadt (DE).
- (72) **Inventors:** KINUTA, Takafumi; Merck Electronics Ltd.,
3330, Chihama, Kakegawa-shi, Shizuoka, 437-1412 (JP).
NAGAHARA, Tatsuro; Merck Electronics Ltd., 3330,
Chihama, Kakegawa-shi, Shizuoka, 437-1412 (JP).

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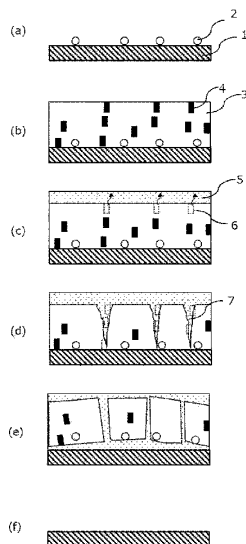
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(54) **Title:** SUBSTRATE CLEANING SOLUTION, METHOD FOR MANUFACTURING CLEANED SUBSTRATE AND
METHOD FOR MANUFACTURING DEVICE

Figure 1



(57) **Abstract:** [Problem] To obtain a substrate cleaning solution capable of cleaning a sub-
strate and removing particles. [Means for Solution] To provide a substrate cleaning solution
comprising an insoluble or hardly soluble solute (A), a soluble solute (B), and a solvent (C),
wherein the solvent (C) comprises water (C-1); and the content of the soluble solute (B) is
0.1 to 500 mass % based on water (C-1).

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